

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of manufacturing a stamper for manufacturing an information medium, comprising the steps of:

manufacturing a photoresist master by forming at least a light absorption layer and a photoresist layer, in that order, on top of a substrate, irradiating light onto said photoresist layer to form a latent image from an opposite surface to that which contacts said light absorption layer, and then developing said latent image to form an uneven pattern;

forming a thin metal film on top of said uneven pattern of said photoresist master;

forming a stamper by forming a metal film on top of said thin metal film, and separating said thin metal film and said metal film from said photoresist master; and

providing a metal catalyst on a surface of said ~~uneven pattern~~, pattern after manufacturing the photoresist master, activating said metal catalyst, and then washing the surface of said uneven pattern on which said metal catalyst is provided with a liquid, as preliminary treatments to the step of forming said thin metal film on said photoresist layer.

2. (Original) The method of manufacturing a stamper for manufacturing an information medium according to claim 1, wherein

pure water is used as said liquid for said washing.

3. (Currently Amended) A stamper for manufacturing an information medium, in a surface of the stamper an uneven pattern being formed in advance, the stamper being manufactured by the steps of: manufacturing a photoresist master by forming at least a light absorption layer and a photoresist layer, in that order, on top of a substrate, irradiating light onto said photoresist layer to form a latent image from an opposite surface to that which

contacts said light absorption layer, and then developing said latent image to form an uneven pattern; forming a thin metal film on top of said uneven pattern of said photoresist master; forming the stamper by forming a metal film on top of said thin metal film, and separating said thin metal film and said metal film from said photoresist master; and providing a metal catalyst on a surface of said ~~uneven pattern~~, pattern after manufacturing the photoresist master, activating said metal catalyst, and then washing the surface of said uneven pattern on which said metal catalyst is provided with a liquid, as preliminary treatments to the step of forming said thin metal film on said photoresist layer.

4. (Original) The stamper according to claim 3, wherein
pure water is used as said liquid for said washing.

5. (Currently Amended) A photoresist master comprising a substrate, a light absorption layer laminated on top of said substrate, and a photoresist layer which is laminated on top of said light absorption layer and ~~is capable of~~ having an uneven pattern formed therein by forming and subsequently developing of a latent image, wherein an activated metal catalyst is provided on a surface of said uneven pattern formed in said photoresist layer, and the surface of said uneven pattern on which said metal catalyst has been provided is washed with a liquid.

6. (Withdrawn-Currently Amended) An information medium, in which a final uneven pattern is formed by using, as a negative pattern, an uneven pattern of a stamper manufactured by the steps of: manufacturing a photoresist master by forming at least a light absorption layer and a photoresist layer, in that order, on top of a substrate, irradiating light onto said photoresist layer to form a latent image from an opposite surface to that which contacts said light absorption layer, and then developing said latent image to form an uneven pattern; forming a thin metal film on top of said uneven pattern of said photoresist master; forming a stamper by forming a metal film on top of said thin metal film, and separating said

thin metal film and said metal film from said photoresist master; and providing a metal catalyst on a surface of said uneven ~~pattern~~, pattern after manufacturing the photoresist master, activating said metal catalyst, and then washing the surface of said uneven pattern on which said metal catalyst is provided with a liquid, as preliminary treatments to the step of forming said thin metal film on said photoresist layer.

7. (Withdrawn) The information medium according to claim 6, wherein said final uneven pattern is formed by direct transfer of said uneven pattern from said stamper.

8. (Withdrawn) The information medium according to claim 6, wherein said final uneven pattern is formed by transfer of an uneven pattern from a mother stamper, and said uneven pattern of said mother stamper is formed by transfer of said uneven pattern using said stamper as a master stamper.

9. (Withdrawn) The information medium according to claim 6, wherein said final uneven pattern is formed by transfer of an uneven pattern from a child stamper, and said uneven pattern of said child stamper is formed by transfer of an uneven pattern from a mother stamper, which has been formed by transfer of said uneven pattern using said stamper as a master stamper.